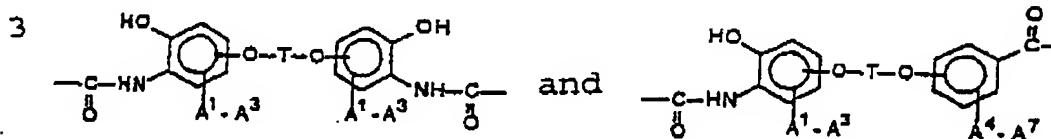


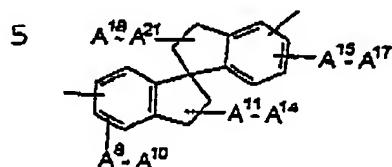
CLAIM AMENDMENTS

Claim 1 (original). A polybenzoxazole precursor comprising a partial structure selected from the group consisting of



wherein each of A¹ to A⁷ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃;

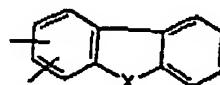
T is a residue selected from the group consisting of



wherein each of A⁸ to A²¹ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃;



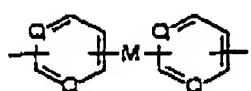
or



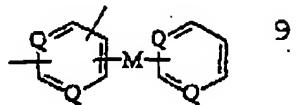
wherein X is selected from the group consisting of -CH₂-, -CF₂-, -C(CH₃)₂-, -C(CF₃)₂-, -C(OCH₃)₂-, -C(OCF₃)₂-, -

) C(CH₃)(C₆H₅)-, -C(C₆H₅)₂-, -O-, -(NH)-, -(N-CH₃)- and -(N-C₆H₅)-;

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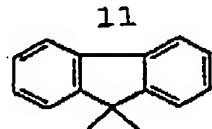


or



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wherein M is selected from the group consisting of residues represented by formulas 10-14



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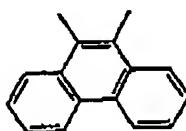


or

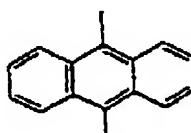
in which Q is selected from the group consisting of C-H, C-F, C-CH₃, C-CF₃, C-OCH₃, C-OCF₃ and N,

and residues represented by formulas 15-34 shown below:

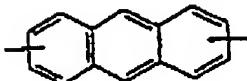
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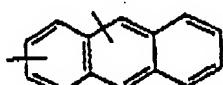
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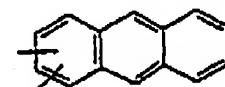
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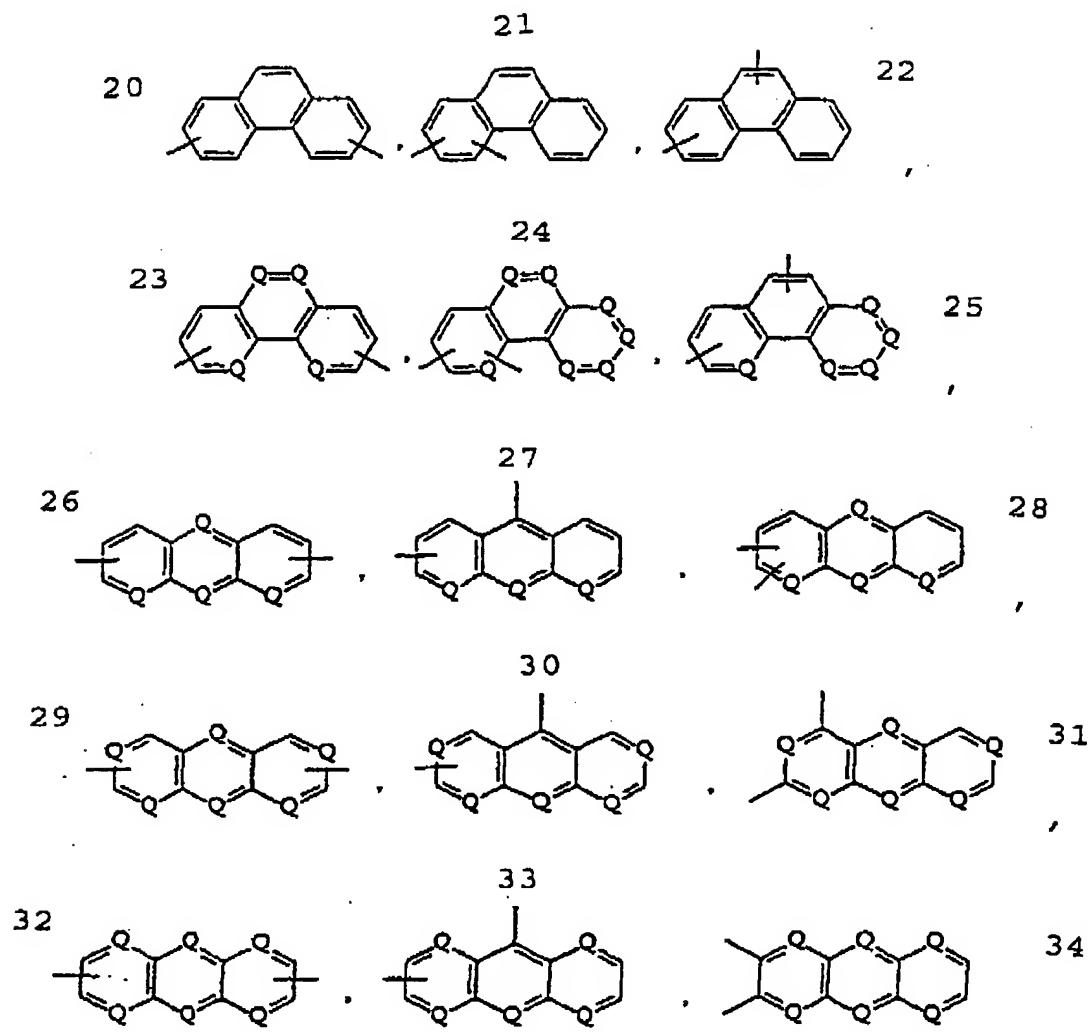


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wherein Q is defined as above, provided that at least one Q signifies N and a maximum of two N atoms are present per ring.

Claim 2 (original). The polybenzoxazole precursor of claim 1, further comprising at least one acetylene group.

)
Claim 3 (original). The polybenzoxazole precursor of
claim 2, wherein said acetylene group is present in the
main chain.

Claim 4 (original). The polybenzoxazole precursor of
claim 2, wherein said acetylene group is present in a side
chain.

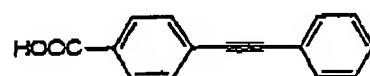
Claim 5 (original). The polybenzoxazole precursor of
claim 2, wherein said acetylene group is present in a
chain terminating group.

Claim 6 (original). The polybenzoxazole precursor of
claim 2, wherein said acetylene group is present in the
residue of a carboxylic acid selected from the group
consisting of

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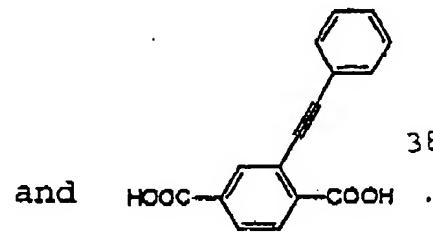


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and

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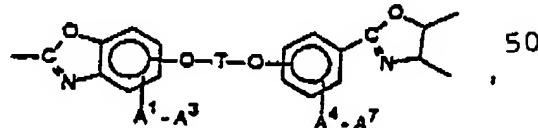
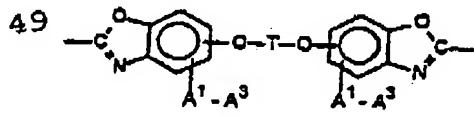


) Claim 7 (original). A photoresist solution, comprising a polybenzoxazole precursor of claim 1, a diazoketone photoactive component, and an organic solvent.

Claim 8 (original). The photoresist solution of claim 7, wherein the weight ratio of polybenzoxazole precursor to diazoketone is in the range from 1:20 to 20:1.

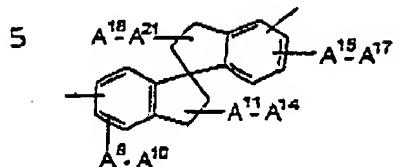
Claim 9 (original). The photoresist solution of claim 8, wherein a weight ratio of polybenzoxazole precursor to diazoketone is in a range from 1:10 to 10:1

Claim 10 (currently amended). A polybenzoxazole containing a partial structure selected from the group consisting of

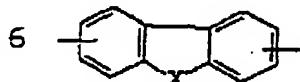


wherein each of A¹ to A⁷ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃; and

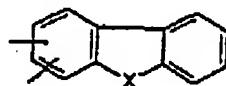
) T is a residue selected from the group consisting of the residues represented by the following formulas 5-34 defined above



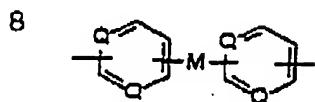
wherein each of A⁸ to A²¹ is a univalent substituent
independently selected from the group consisting of H, F,
CH₃, CF₃, OCH₃ and OCF₃;



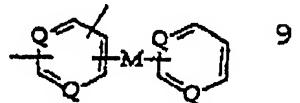
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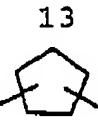
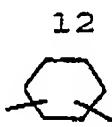
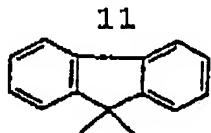
wherein X is selected from the group consisting of -CH₂-,
-CF₂-, -C(CH₃)₂-, -C(CF₃)₂-, -C(OCH₃)₂-, -C(OCF₃)₂-,
C(CH₃)(C₆H₅)-, -C(C₆H₅)₂-, -O-, -(NH)-, -(N-CH₃)- and -(N-
C₆H₅)-;



or



wherein M is selected from the group consisting of
residues represented by formulas 10-14

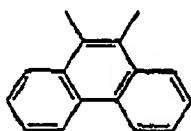


or

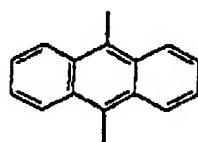
in which Q is selected from the group consisting of C-H,
C-F, C-CH₃, C-CF₃, C-OCH₃, C-OCF₃ and N,

) and residues represented by formulas 15-34 shown below:

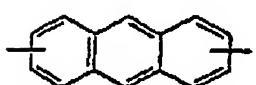
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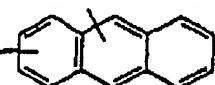
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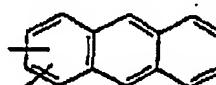
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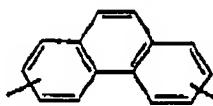
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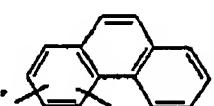
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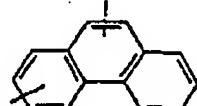
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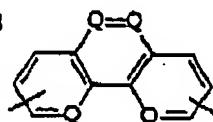
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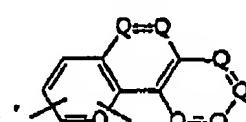
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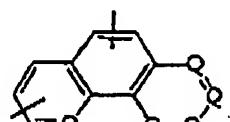
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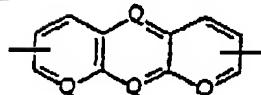
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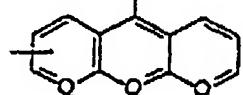
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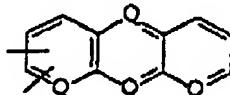
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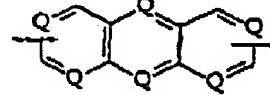
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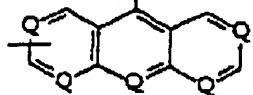
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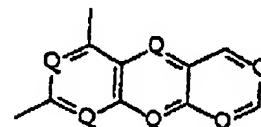
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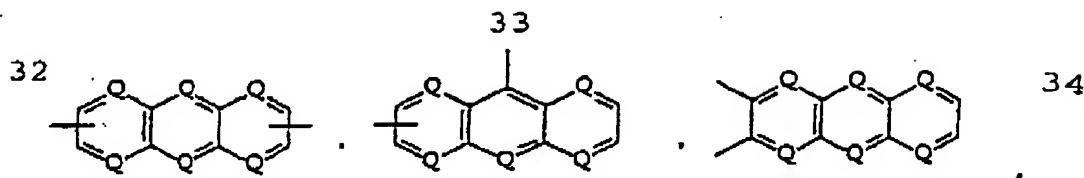


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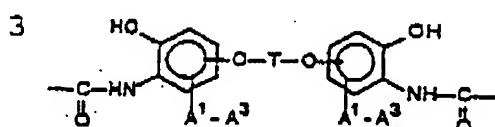
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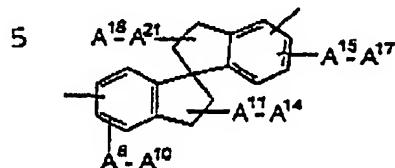
wherein Q is defined as above, provided that at least one Q signifies N and a maximum of two N atoms are present per ring.

Claim 11 (currently amended). The polybenzoxazole precursor of claim 1, wherein said partial structure is

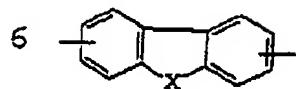


wherein each of A¹ to A³ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃; and

T is a residue selected from the group consisting of the residues represented by the following formulas 5-34 defined above



wherein each of A⁸ to A²¹ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCF₃;

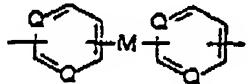


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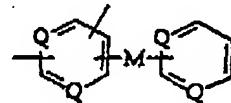


wherein X is selected from the group consisting of -CH₂-,
-CF₂-, -C(CH₃)₂-, -C(CF₃)₂-, -C(OCH₃)₂-, -C(OCF₃)₂-, -C(CH₃)(C₆H₅)-,
-C(C₆H₅)₂-, -O-, -(NH)-, -(N-CH₃)- and -(N-C₆H₅)-;

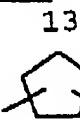
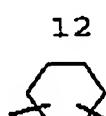
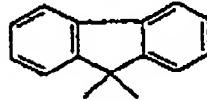
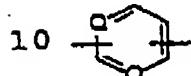
8



or



wherein M is selected from the group consisting of residues represented by formulas 10-14



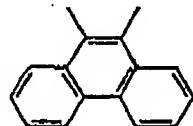
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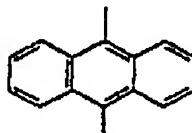
in which Q is selected from the group consisting of C-H, C-F, C-CH₃, C-CF₃, C-OCH₃, C-OCF₃ and N,

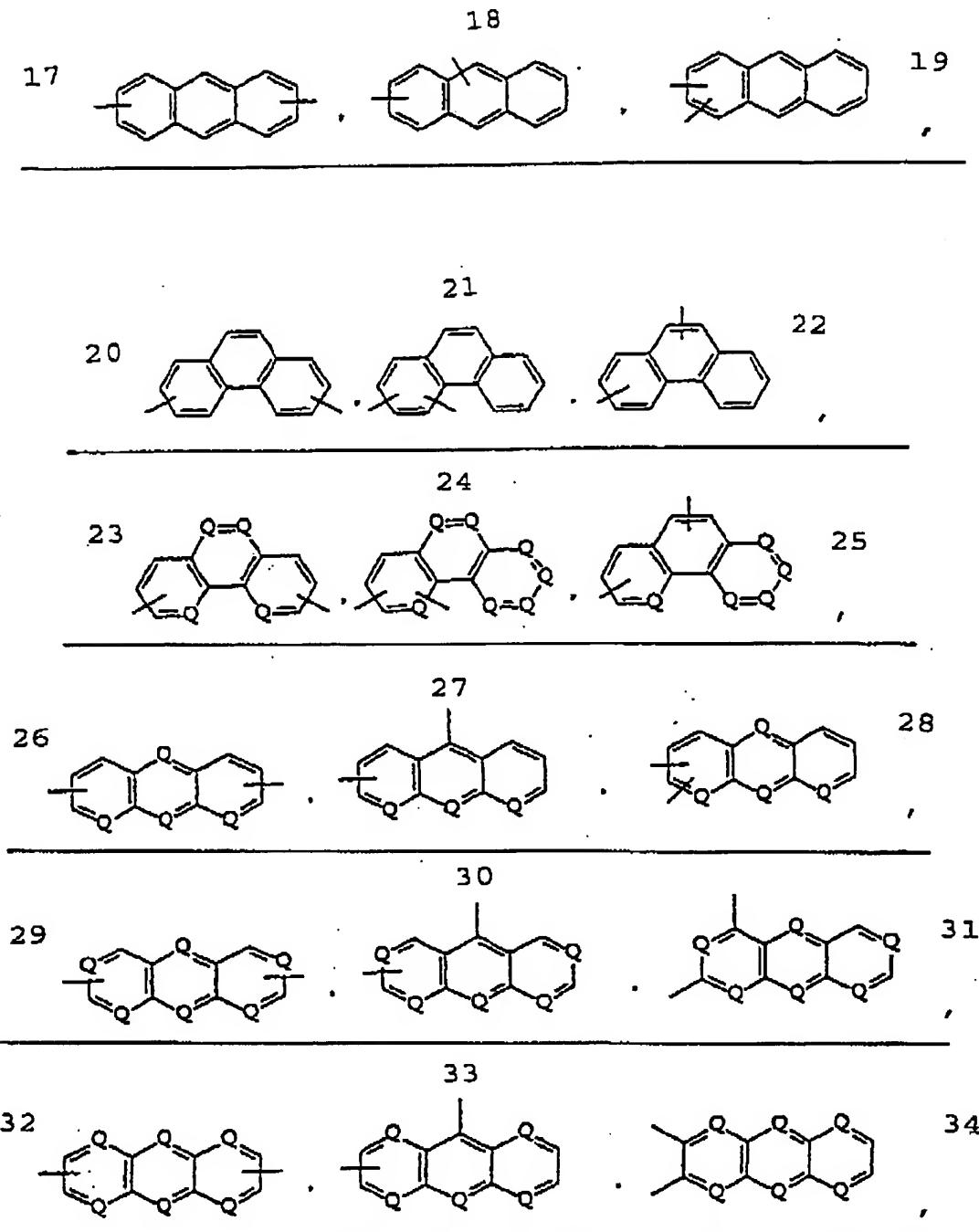
and residues represented by formulas 15-34 shown below:

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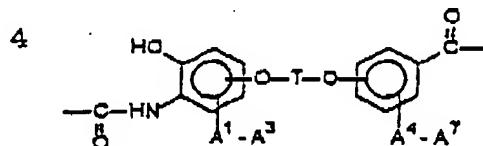
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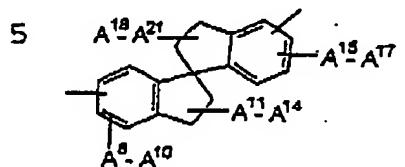
wherein Q is defined as above, provided that at least one
Q signifies N and a maximum of two N atoms are present per
ring.

Claim 12 (currently amended). The polybenzoxazole precursor of claim 1, wherein said partial structure is

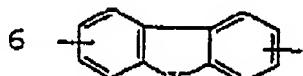


wherein each of A¹ to A⁷ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCFC₃; and

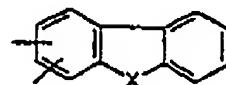
T is a residue selected from the group consisting of the residues represented by the following formulas 5-34 defined above



wherein each of A⁸ to A²¹ is a univalent substituent independently selected from the group consisting of H, F, CH₃, CF₃, OCH₃ and OCFC₃;



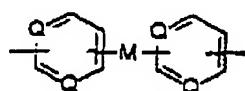
or



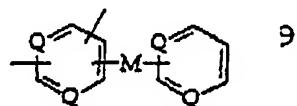
wherein X is selected from the group consisting of -CH₂-,-CF₂-,-C(CH₃)₂-,-C(CF₃)₂-,-C(OCH₃)₂-,-C(OCFC₃)₂-,-

C(CH₃)(C₆H₅)-, -C(C₆H₅)₂-, -O-, -(NH)-, -(N-CH₃)- and -(N-C₆H₅)-;

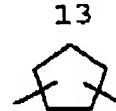
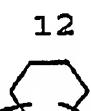
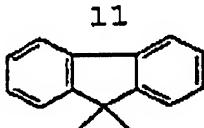
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or



wherein M is selected from the group consisting of residues represented by formulas 10-14



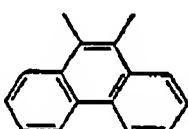
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or

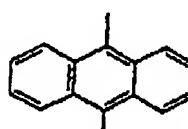
in which Q is selected from the group consisting of C-H, C-F, C-CH₃, C-CF₃, C-OCH₃, C-OCE₃ and N,

and residues represented by formulas 15-34 shown below:

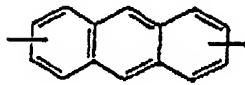
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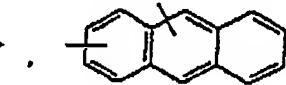
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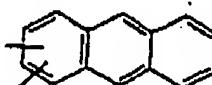
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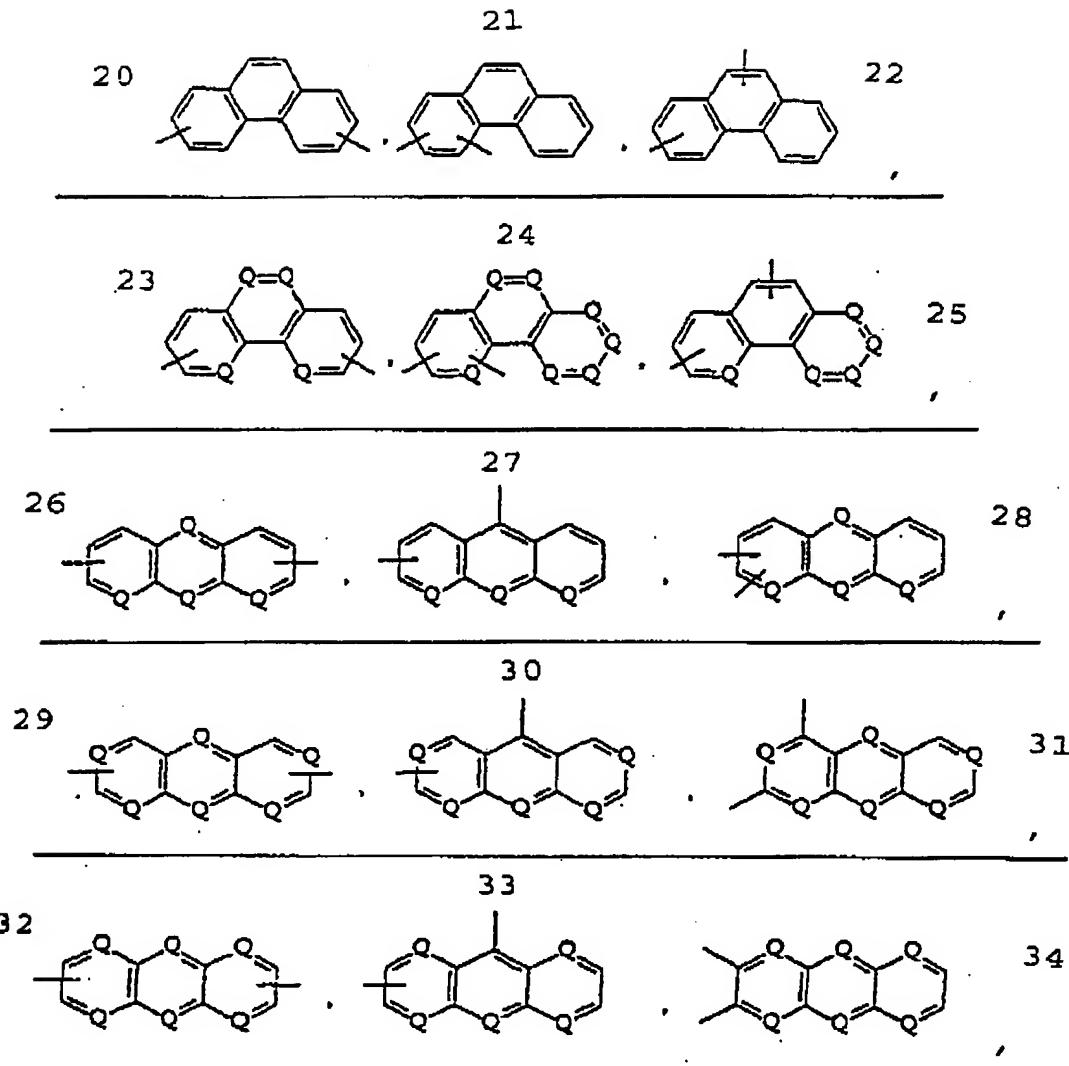


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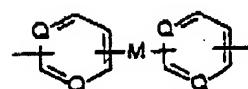


wherein Q is defined as above, provided that at least one Q signifies N and a maximum of two N atoms are present per ring.

) Claim 13 (original). The polybenzoxazole precursor of claim 1, wherein each of A¹ to A⁷ is H.

) Claim 14 (original). The polybenzoxazole precursor of
claim 1, wherein T is

8



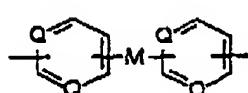
in which each Q is CH and M is

11



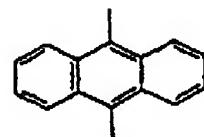
) Claim 15 (original). The polybenzoxazole precursor of
claim 1, wherein T is

8



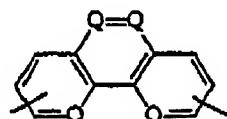
in which each Q is CH and M is

16



) Claim 16 (original). The polybenzoxazole precursor of
claim 1, wherein T is

23

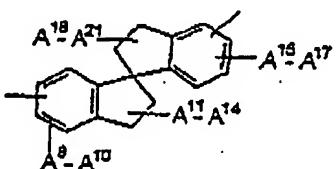


-16-

) in which Q in each outside ring is N and each Q in the middle ring is CH.

Claim 17 (original). The polybenzoxazole precursor of claim 1, wherein T is

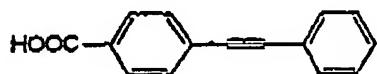
5



in which six of the substituents A⁸ to A²¹ are CH₃ and the remainder of the substituents A⁸ to A²¹ are H.

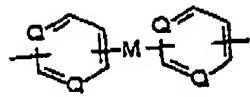
Claim 18 (original). The polybenzoxazole precursor of claim 5, wherein said chain terminating group is a residue of

36



) Claim 19 (original). The polybenzoxazole precursor of claim 18, wherein T is

8



in which each Q is CH and M is

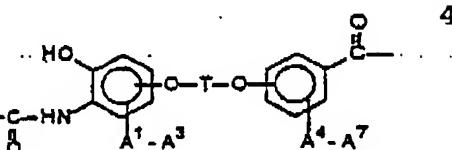
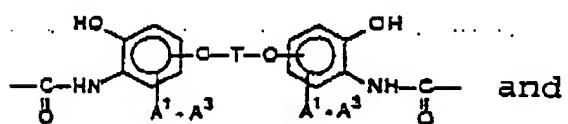
)

11



Claim 20 (original). A process for preparing a polybenzoxazole precursor containing a partial structure selected from the group consisting of

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wherein each of A¹ to A⁷ and T are as defined above, comprising the steps of

providing at least one reactant selected from the group consisting of bis-o-aminophenols and o-aminophenolcarboxylic acids,

causing the reactant to react with at least one dicarboxylic acid compound,

) mixing the reaction mixture with a precipitating agent to precipitate a solid polybenzoxazole precursor,

and isolating the polybenzoxazole precursor from the reaction mixture.